## Amendment to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application. Claim 19 is herein canceled without prejudice. Please add new claims 32 and 33.

## **Listing of Claims:**

1. – 12. (Canceled)

13. (Currently amended) A method comprising:

depositing a first metallic film and a second metallic film on a substrate proximate to a second metallic film;

depositing a layer of photoresist on at least the first metallic film;

patterning the photoresist such that a desired portion of the first metallic film is masked and an undesired portion of the first metallic film is exposed;

selecting two or more chelating agents based upon the metals contained in the first metallic film; and

using the two or more chelating agents to remove the undesired portion of the first metallic film, wherein the two or more chelating agents do not impair the second metallic film.

14. (Previously presented) The method of claim 13 further comprising:

App. No. 10/658,225 Docket No. 42.P17298 Examiner: K. Duda Art Unit: 1756 selecting a media in which to employ the two or more chelating agents based upon the metals contained in the first metallic film.

15. (canceled)

16. (Previously presented) The method of claim 13 wherein the two or more chelating agents are employed in a solution at a concentration ranging from approximately 0.5 - 5 moles/liter, for each chelating agent.

17. (Previously presented) The method of claim 14 wherein the two or more chelating agents are employed in a solution selected from the group consisting of an acidic solution, a basic solution, a solvent solution, and a de-ionized water solution.

18. (Currently amended) A method comprising:

depositing a first metallic film and a second metallic film on a substrate proximate to a second metallic film;

depositing a layer of photoresist on at least the first metallic film;

patterning the photoresist such that a desired portion of the first metallic film is masked and an undesired portion of the first metallic film is exposed;

selecting a media in which to employ two or more chelating agents based upon the metals contained in the first metallic film; and

App. No. 10/658,225 Docket No. 42.P17298 Examiner: K. Duda Art Unit: 1756

5

employing the two or more chelating agents to remove the undesired portion of the first metallic film, wherein the two or more chelating agents do not impair the

second metallic film.

19. (Canceled)

20. (Currently amended) The method of claim 18 [[19]] wherein the media is a liquid

media selected from the group consisting of an aqueous acid media with oxidant, an

aqueous acid media without oxidant, an aqueous basic media without oxidant, and a

solvent media without oxidant having a pH of approximately seven.

21. (Previously presented) The method of claim 18 wherein the two or more chelating

agents are employed in a solution at a concentration ranging from approximately 0.5-5

moles/liter, for each chelating agent.

22. (Currently amended) The method of claim 13 wherein the two or more chelating

agents are used in proportion to a [[the]] proportion of the respective metals of the first

metallic film.

23. (Currently amended) The method of claim 13 wherein the two or more chelating

agents are specifically tailored to bind with [[the]] metals in the first metallic film.

6 Examiner: K. Duda App. No. 10/658,225 Docket No. 42.P17298 Art Unit: 1756 24. (Currently amended) The method of claim 18 wherein the two or more chelating agents are used in proportion to <u>a</u> [[the]] proportion of the respective metals of the first metallic film.

25. (Currently amended) The method of claim 18 wherein the two or more chelating agents are specifically tailored to bind with [[the]] metals in the first metallic film.

26. – 31. (canceled)

32. (New) The method of claim 13 wherein said first metallic film is an alloy comprised of at least two different metals.

33. (New) The method of claim 18 wherein said first metallic film is an alloy comprised of at least two different metals.